

FORM PTO-1449

INFORMATION DISCLOSURE STATEMENT

ATTY. DOCKET NO.
1857.1560001APPLICATION NO.
10/688,923APPLICANT
Augustyn *et al.*FILING DATE
October 21, 2003GROUP
2872

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE
<i>FA</i>	AA1	US 2003/0081316 A1	05/2003	Goldberg <i>et al.</i>			09/17/2001
<i>BA</i>	AB1	6,392,792 B1	05/2002	Naulleau			
	AC1						
	AD1						
	AE1						
	AF1						
	AG1						
	AH1						
	AI1						
	AJ1						
	AK1						

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION
	AL1						Yes No
	AM1						Yes No
	AN1						Yes No
	AO1						Yes No
	AP1						Yes No

OTHER (Including Author, Title, Date, Pertinent Pages, etc.)

<i>FA</i>	AR	1	Bjorkholm, J. E., "EUV Lithography - The Successor to Optical Lithography?", Intel Technology Journal Q3'98, 1998, pp. 1-8.
<i>FA</i>	AS	1	Goldberg, K.A., <i>et al.</i> , "Extreme ultraviolet interferometry: at-wavelength testing of optics for lithography," The Advanced Light Source, 1998, <i>at</i> http://www-als.lbl.gov/als/compendium/AbstractManager/uploads/ACF4B6D.pdf , 4 pages.
<i>FA</i>	AT	1	Goldberg, K.A., <i>et al.</i> , "Extreme ultraviolet interferometry: measuring EUV optical systems with sub-Å accuracy," The Advanced Light Source, 2001, <i>at</i> http://www-als.lbl.gov/als/compendium/AbstractManager/uploads/01125.pdf , 3 pages.

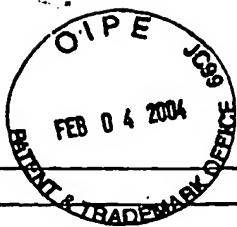
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DATE CONSIDERED

11/6/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.



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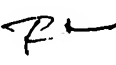

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE
	AA2						
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	AC2						
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	AE2						
	AF2						
	AG2						
	AH2						
	AI2						
	AJ2						
	AK2						

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION
	AL2						Yes No
	AM2						Yes No
	AN2						Yes No
	AO2						Yes No
	AP2						Yes No

OTHER (Including Author, Title, Date, Pertinent Pages, etc.)

	AR	2	Kolb, R., "EUV Lithography Making Possible Next Generation of Semiconductors," Sciencebeat [online], June 5, 2001, at http://www.tbl.gov/Science-Articles/Archive/euv_milestone.html (visited January 12, 2003), 4 pages.
	AS	2	Lee, S. H., <i>High Accuracy EUV Interferometry</i> , at http://buffy.eecs.berkeley.edu/IRO/Summary/99abstracts/shlee.1.html (visited January 12, 2003), 1 page.
	AT	2	Mansuripur, M., "The Ronchi Test," MM Research, Inc., at http://www.mmresearch.com/articles/article1/ (visited January 9, 2003), 12 pages (also published in <i>Optics & Photonics News</i> , July 1997, pp.42-46).

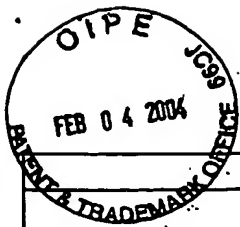
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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE
	AA3						
	AB3						
	AC3						
	AD3						
	AE3						
	AF3						
	AG3						
	AH3						
	AI3						
	AJ3						
	AK3						

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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION
	AL3						Yes No
	AM3						Yes No
	AN3						Yes No
	AO3						Yes No
	AP3						Yes No

OTHER (Including Author, Title, Date, Pertinent Pages, etc.)

	AR	3	Naulleau, P. P., <i>et al.</i> , "Fabrication of high-efficiency multilayer-coated binary blazed gratings in the EUV regime," <i>Optics Communications</i> , Vol. 200, December 15, 2001, Elsevier Science B.V., pp. 27-34.
	AS	3	<i>Measurement Science in the Extreme Ultraviolet: Testing Advance Optics for Printing Integrated Circuits</i> , at http://www-als.lbl.gov/als/actrep/FileH.pdf (visited January 12, 2003), 2 pages.
	AT	3	Wyant, J. C., "White Light Extended Source Shearing Interferometer," <i>Applied Optics</i> , Vol. 13, No. 1, January 1974, pp. 200-202.

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FORM PTO-1449
**SUPPLEMENTAL
 INFORMATION DISCLOSURE STATEMENT**

ATTY. DOCKET NO.
 1857.1560001

APPLICATION NO.
 10/688,923

FIRST NAMED INVENTOR
 Augustyn *et al.*

FILING DATE
 October 21, 2003

ART UNIT
 2872

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE
	AC1	5,641,593	06/1997	Watanabe <i>et al.</i>		
	AD1	6,163,405	12/2000	Chang <i>et al.</i>		
	AE1	2001/0051304 A1	12/2001	Stivers <i>et al.</i>		
	AF1					
	AG1					
	AH1					
	AI1					
	AJ1					
	AK1					

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION
TA	AL1	JP 2000-266914	09/2000	Japan		X Yes No
	AM1					Yes No
	AN1					Yes No
	AO1					Yes No
	AP1					Yes No

OTHER (Including Author, Title, Date, Pertinent Pages, etc.)

AR	4	Copy of a Search Report from the Danish Patent and Trademark Office for Singapore Patent Application No. 200400112-9, mailed August 20, 2004 (7 pages).
AS	4	English-language abstract for Japanese Patent No. 2000-266914, published September 29, 2000, from www.espacenet.com, 1 page.
AT	4	

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